

ABSTRACT OF THE DISCLOSURE

5 A method of forming an oxide structure and an oxide structure formed by the method. In one embodiment a lower cladding layer on a substrate is provided. At least one core layer is formed on lower cladding layer, the core layer includes boron at a concentration that produces substantially zero internal stress of said core layer. At least one upper cladding layer is formed on the core layer wherein at least one of the upper and lower cladding layers include germanium at a concentration level such that the upper and lower cladding layers exhibit substantially equivalent refractive indices.



G00002



162162